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Research

Light Trapping Effect of Submicron Surface Textures in Crystalline Si Solar Cells

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Recently, submicron textures have been researched and applied to multicrystalline silicon solar cells in order to improve their optical performance. In this study, the antireflection and light trapping effects of submicron surface textures in crystalline Si (c-Si) solar cells were quantitatively investigated by numerical simulations based on Maxwell's equations with a simple two-dimensional (2D) surface grating model. The calculated results showed that the surface reflection loss can be effectively reduced by using submicron Si surface gratings with appropriate aspect ratios. On the other hand, higher order diffractions that are caused by surface gratings that increase optical path lengths and light absorption near the band gap wavelength are dominant only for those with periods greater than 0.5 µm. From these results, it was inferred that submicron textures are effective for light trapping as well as for antireflection in thin c-Si solar cells if appropriate dimensions are chosen. Copyright © 2007 John Wiley & Sons, Ltd.

KEY WORDS: light trapping; surface texturing; submicron texture; antireflection; crystalline Si; diffraction

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INTRODUCTION

he global production of crystalline Si (c-Si) solar cells has been growing rapidly for the past 10 years; however, a further reduction in cost by using thinner Si substrates (\sim 50 μ m) is required since the substrate cost comprises approximately half the cell module cost. Light trapping is more important in developing high-efficiency c-Si solar cells with thinner substrates because the absorption coefficient is substantially small near the bandgap wavelength (e.g., \sim 100 cm⁻¹ at 1·0 μ m). In general, surface texturing is widely used as a light confinement technique. By developing the surface structure on a Si substrate, the following three effects can be observed: (a) reduction in surface reflection, (b) increase in light absorption due to an increase in optical path length by diffraction, and (c) enhancement of internal reflection that reduces the amount of escaping light. Effect (a) is essential for increasing the input energy to solar cells, irrespective of the cell thickness. For thin Si substrates, effects (b) and (c) are vital for increasing light absorption at higher wavelengths.

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Single c-Si solar cells are generally textured with random pyramids, which are produced by anisotropic wet chemical etching solutions such as those of KOH and NaOH. In most of the cases, the random pyramids have dimensions in the range of several microns. The random nature of multicrystalline Si (mc-Si) makes such techniques considerably less effective for this material. For the past 10 years, surface texturing by dry processes such as reactive ion etching (RIE) has been investigated and applied to mc-Si solar cells. ^{2–5} By this technique, it is possible to uniformly produce very fine structures in the submicron range on a Si surface; moreover, the surface reflectivity can be reduced effectively. However, few studies have systematically and quantitatively investigated the light trapping effect of such submicron structures. The main reason is the difficulty in the optical analysis of such small structures. The optical properties of submicron textures in the visible and near infrared wavelengths cannot be quantitatively evaluated by a simple analysis based on the scalar theory such as the ray-tracing technique, in which the wavelengths of light are assumed to be sufficiently smaller than the typical dimensions of objects. 1,6,7 Therefore, more rigorous approaches are required. Thus, Abouelsaood et al. have rigorously analyzed the light trapping effect of submicron Si gratings based on coupled-wave analysis. On the other hand, Heine and Morf9 have measured the light trapping effect caused by well-defined submicron Si gratings on the rear side of c-Si solar cells. However, they have considered only one-dimensional gratings; therefore, further investigations are required.

In this study, the optical properties of submicron structures were evaluated with the help of numerical simulations. The diffraction (refraction) and surface reflection due to submicron surface structures were investigated from the viewpoint of light trapping in c-Si solar cells.

SIMULATION METHOD

We conducted numerical calculations on the basis of a rigorous coupled-wave analysis (RCWA),¹⁰ which is a method that can be used to directly solve the Maxwell's electromagnetic equations. In a previous paper, we showed that the simulated results obtained by RCWA agree well with the experimental data, and that RCWA is an effective tool for estimating the optical behavior of submicron textures.¹¹

For simplicity, the submicron textures investigated in this study were modeled by two-dimensional (2D) surface gratings composed of small pyramids without antireflective coatings. The pyramid grating region was symmetrical along the x and y directions and was approximated by a stack of 8 or 16 layers of Si slabs, as shown in Figure 1. The calculation parameters were the period Λ , grating depth d, and substrate thickness w. For some cases, an Al back surface reflector (BSR) was applied to the smooth rear surface. In all the calculations, the diffraction efficiencies, DE_{mn} , up to ± 7 th were taken into account, where m and n are the diffraction orders for the x and y directions, respectively. In order to reduce the calculation time, plane waves with a fixed polarization angle of 45° were used as the incident light instead of a randomly polarized light. This is a good assumption of randomly polarized sunlight because the optical properties of 2D symmetrical gratings are essentially not

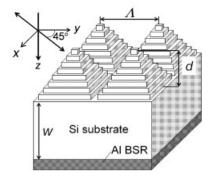


Figure 1. The Si cell model with submicron surface textures used for calculations in this study. Λ : period, d: grating depth, w: substrate thickness. For calculating surface reflection, the Si substrate was assumed to have infinite thickness

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sensitive to the polarization angle of the incident light. The optical constants of Si and Al were obtained from the literature. 12,13

RESULTS AND DISCUSSION

Surface reflection

First, the surface reflectivity of the submicron textures was calculated by assuming that the Si substrate was infinitely thick. The surface reflectivity is of prime importance for increasing the photovoltaic energy conversion efficiencies because it determines the amount of light that enters into the cells and forms electron-hole pairs. Figure 2 shows the calculated spectral reflectivity of the 2D Si gratings at normal incidence for several different values of Λ under a constant aspect ratio, $d/\Lambda=1\cdot0$. The reflectivity is decreased by developing the submicron textures over a wide range of wavelengths. This figure also shows that the reflectivity can be substantially decreased by increasing Λ from $0\cdot1~\mu m$ to $0\cdot4~\mu m$ for a constant value of d/Λ . Figure 3 shows the reflectivity spectra for several different values of d under a constant period, $\Lambda=0\cdot2~\mu m$. The reflectivity can also be reduced by increasing d over a wide range of wavelengths, as shown in the figure. Figure 3 indicates that a very low reflectivity of less than 2% can be obtained by fabricating the surface gratings with a high aspect ratio, that is, $d/\Lambda>2\cdot0$, for this case.

We calculated the surface reflectivity spectra of the submicron Si gratings for various values of Λ and d and determined the weighted reflectivity for the standard solar spectrum by the following equation:

$$R_{\text{solar}} = \frac{\int\limits_{0.3\,\mu\text{m}}^{1.12\,\mu\text{m}} R(\lambda) N_{\text{photon}}(\lambda) d\lambda}{\int\limits_{0.3\,\mu\text{m}}^{1.12\,\mu\text{m}} N_{\text{photon}}(\lambda) d\lambda}$$
(1)

where $R(\lambda)$ is the spectral reflectivity of the textured surfaces and $N_{\rm photon}$ is the photon number of the solar irradiation (AM1·5G) per unit area per unit wavelength. The bandgap wavelength of c-Si was set to 1·12 μ m. The results shown in Figure 4 indicate that a low value of $R_{\rm solar}$ of less than 3% can be obtained by using a variety of submicron surface gratings. For $\Lambda > 0.4 \,\mu$ m, a low value of $R_{\rm solar}$ can be obtained with a reasonable value of

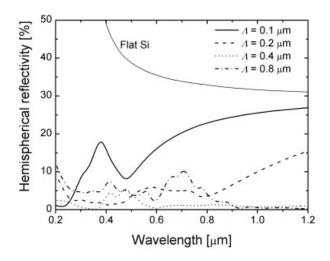


Figure 2. Calculated spectral reflectivity of submicron Si surface gratings for several values of Λ under a constant aspect ratio, $dl\Lambda = 1.0$, at normal incidence

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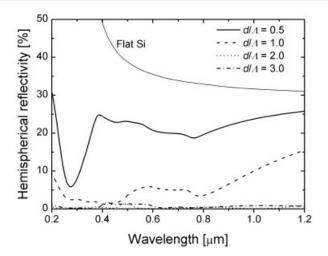


Figure 3. Calculated spectral reflectivity of submicron Si surface gratings with $\Lambda = 0.2 \,\mu m$ for several values of d/Λ at normal incidence

 d/Λ (around unity). On the other hand, for small values of Λ of less than $0.2~\mu m$, a much larger value of d/Λ is required to reduce the surface reflection loss at the same level. A larger aspect ratio naturally results in a larger surface area, which enhances the surface recombination in solar cells. From these results, it is inferred that a submicron texture with $\Lambda > 0.4~\mu m$ is effective for reducing the surface reflection loss without severe surface recombination loss.

Forward diffraction

Once light enters into a solar cell with a surface grating, it propagates through the solar cell at a particular diffraction angle based on the diffraction order, schematically shown in Figure 5. The forward diffraction angle

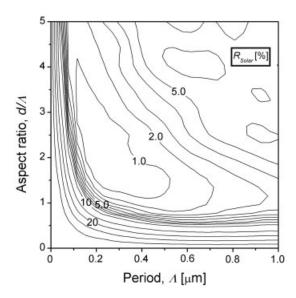


Figure 4. Contour map of the weighted reflectivity of submicron Si gratings as functions of Λ and d/Λ for the standard solar spectrum (AM1.5)

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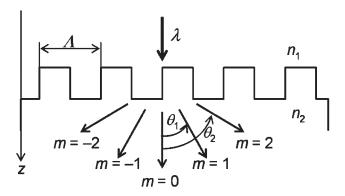


Figure 5. Schematic drawing of forward diffraction by 1D surface grating

 θ_m of a one-dimensional surface grating is given by the following equation:¹⁴

$$n_2 \sin \theta_m = n_1 \sin \theta_i + m \frac{\lambda}{\Lambda} \tag{2}$$

where n_1 and n_2 are the refractive indices of mediums 1 and 2, respectively. Further, θ_i , the incident angle; θ_m , the diffraction angle at the diffraction order m ($m = 0, \pm 1, \ldots$); and λ , the wavelength. A similar expression is obtained for the backward diffraction, namely, reflection.

In the case of 2D Si gratings, the diffraction angles for normal incidence are given by:

$$n_{Si}\sin\theta_{mn}\cos\phi_{mn} = m\frac{\lambda}{\Lambda_x} \tag{3-1}$$

$$n_{Si}\sin\theta_{mn}\sin\phi_{mn} = n\frac{\lambda}{\Lambda_{v}} \tag{3-2}$$

where θ_{mn} and ϕ_{mn} are the diffraction polar angle and the azimuthal angle at the diffraction order of (m, n), respectively. Note that the diffraction angles are basically independent of the grating depth, d.

Figure 6 shows the values of θ_{mn} of symmetrical 2D gratings $(\Lambda = \Lambda_x = \Lambda_y)$ as functions of normalized wavelengths, λ/Λ , for several sets of diffraction orders. In this figure, a constant refractive index $(n_{Si} = 3.6)$ was considered. Figure 6 reveals that no high order diffractions occur in the case of $\lambda/\Lambda > 4$. For such structures, the entire incident light propagates through the medium in a straight direction. This is a typical behavior of

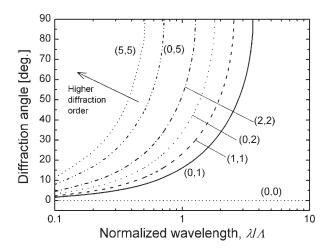


Figure 6. Diffraction angles θ_{mn} as functions of normalized wavelength, λ/Λ at several diffraction orders (m, n) for 2D symmetrical Si grating $(n_{Si} = 3.6)$

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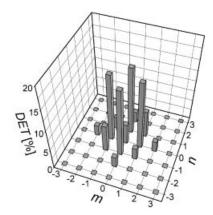


Figure 7. Distribution of the forward diffraction efficiencies DET_{mn} of 2D Si pyramid grating with $\Lambda = 0.6 \,\mu\text{m}$ and $d/\Lambda = 1.0 \,\mu\text{m}$

subwavelength structures whose Λ is much lesser than λ ($\lambda/\Lambda >> 1$). This result shows that very small structures are not effective for increasing the optical path lengths by diffraction.

The next question is how the transmitted light is distributed between each diffraction order, in other words, each diffraction angle. The forward (transmission) diffraction efficiencies for each diffraction order (m, n), DET_{mn}, can be obtained by RCWA calculations. Figure 7 shows the calculated DET distribution for the 2D Si pyramid grating with $\Lambda = 0.6 \,\mu\text{m}$ and $d/\Lambda = 1.0 \,\mu\text{m}$. In this case, most of the transmitted light is distributed between the $(0, \pm 1)$ and $(\pm 1, 0)$ orders and the DET₀₀ value is only 5%. The light distributed among the higher orders, particularly, $(m, n) \neq (0, 0)$, propagates through Si at oblique angles. Consequently, there is an increase in the light absorption in the c-Si solar cells with finite thicknesses, particularly for longer wavelengths at which the absorption coefficient of c-Si is small.

Here, we define DET for higher orders, DET_{HO}, which quantifies the contribution to light trapping as follows:

$$DET_{HO} = \sum_{m=-\infty}^{\infty} \sum_{n=-\infty}^{\infty} DET_{mn} - DET_{00}$$
(4)

DET_{HO} is the summation of DET_{mn} for all DET values except DET₀₀. In this study, the summation was performed in the range from -7 to +7. In Figure 8, DET_{HO} is plotted as a function of wavelength for several Si pyramid gratings with $d/\Lambda = 1.0$. The absorption length (reciprocal of absorption coefficient) of c-Si is also plotted for comparison. For increasing values of Λ , DET_{HO} increases up to approximately 100% for

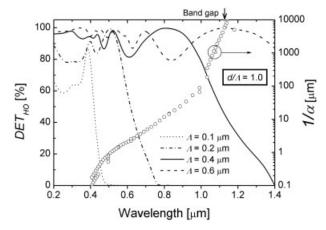


Figure 8. Higher order DET of 2D Si pyramid gratings with $d/\Lambda = 1.0$ as a function of wavelength for several different values of Λ . The circular symbols show the absorption length of c-Si¹²

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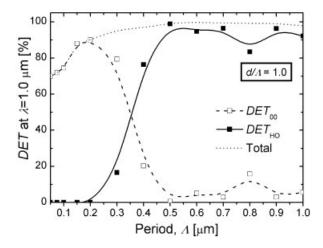


Figure 9. DET of 2D Si pyramid gratings with $d/\Lambda = 1.0$ as a function of Λ at $\lambda = 1.0 \,\mu m$

longer wavelengths at which the absorption coefficient of c-Si is small. This contributes to effective light trapping in c-Si solar cells made of thin substrates.

In Figure 9, DET is plotted as a function of Λ at a constant wavelength, $\lambda=1.0~\mu m$. The behavior of DET can be categorized into three regions: the region where only DET $_{00}$ is generated (region 1), the region where DET $_{HO}$ is dominant (region 2), and the transient region (region 3). Clearly, region 2 is preferable from the viewpoint of light trapping. From Figure 9, it is inferred that surface textures larger than $0.5~\mu m$ are suitable for achieving effective light trapping in thin c-Si cells as well as for achieving low surface reflectivity.

Cell structure

In the previous two sections, the surface reflection and the diffraction of the submicron Si gratings were discussed for a Si substrate that was assumed to have infinite thickness. In the following section, we consider a Si cell model with a finite substrate thickness w and a rear Al-BSR, as shown in Figure 1. In this case, the effect of transmitted light behind the cell structure is considered negligible. Under this assumption, all the incident photons are finally absorbed inside Si or lost in the following three ways: reflection at the front surface, absorption at the rear Al-BSR, and escape from the cell without absorption. A sum of the above mentioned three losses provide the optical loss of the cell structure. Note that our calculations throughout this paper are on the basis of the properties of steady state solutions, and therefore, the effect of multiple internal reflections inside the cell model was taken into account.

Figure 10 shows the w dependence of the optical loss of a Si cell structure with a 2D submicron grating on the front surface and an Al-BSR on the flat rear surface. In this figure, the values of Λ and d are fixed to 0·1 and 0·4 μ m, respectively. These loss spectra show the percentage of non-absorbed photons inside the Si cells. The optical loss near the bandgap wavelength increases with a decrease in w because of the imperfect light trapping of the cell structure.

The spectral optical loss of Si cell structures with different values of Λ and d was calculated in the same manner as that shown in Figure 10. With those results, the total optical loss of the cell structures for the standard solar spectrum was evaluated by the following equation:

Loss =
$$\frac{\int\limits_{0.3\,\mu\text{m}}^{1\cdot12\,\mu\text{m}} (1 - \text{Abs}(\lambda)) N_{\text{photon}}(\lambda) d\lambda}{\int\limits_{0.3\,\mu\text{m}}^{1\cdot12\,\mu\text{m}} N_{\text{photon}}(\lambda) d\lambda}$$
(5)

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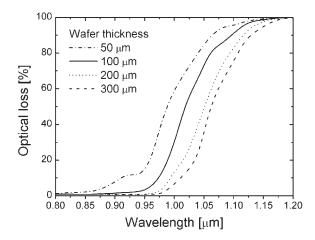


Figure 10. Calculated optical loss spectra of c-Si cell models with a surface texture and rear Al-BSF for several substrate thicknesses w. The surface texture is the 2D pyramid grating with $\Lambda = 0.1 \,\mu$ m and $d/\Lambda = 4.0$

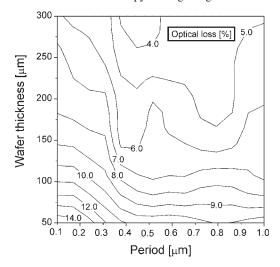


Figure 11. Calculated total optical loss of c-Si cell model with a surface texture and rear Al-BSF as functions of w and Λ . For each Λ , d/Λ was set to the value providing the lowest R_{solar} value according to Figure 4

where Abs is the ratio of the photons absorbed by the Si part of the cell model to the total incident photons. Figure 11 shows the optical loss of the Si cells with submicron-textured surfaces as a function of the wafer thickness, w. For each value of Λ , d/Λ was set such that the lowest value of $R_{\rm solar}$ was obtained, according to Figure 4. As expected, the larger the value of w, the smaller is the optical loss. Surface gratings with smaller values of Λ yield higher optical losses than those with larger values of Λ for the same value of w, whereas all the textures considered here provided low values of $R_{\rm solar}$ of below 3%, as shown in Figure 4. This tendency is particularly observed for thinner substrates having thicknesses of less than 100 μ m. This significant loss is attributed to the short optical path length, which is caused by the amount of higher order diffractions being less, as shown in Figure 9.

CONCLUSIONS

In this study, the antireflection and light trapping effects of submicron surface textures in c-Si solar cells were quantitatively investigated by means of numerical simulations with a simple 2D Si surface grating model, and

two informative results were obtained. First, surface reflection loss can be effectively reduced by using submicron Si gratings over a wide range of periods $(0\cdot1-1\cdot0\,\mu\text{m})$ and appropriate aspect ratios; however, smaller textures less than $0\cdot2\,\mu\text{m}$ require much higher aspect ratios in order to realize a low reflection loss. Second, higher order diffractions by the submicron textures increase the optical path lengths inside c-Si, and periods larger than $0\cdot5\,\mu\text{m}$ are preferable to obtain this effect at higher wavelengths $(0\cdot9-1\cdot1\,\mu\text{m})$ where light trapping is important. From these results, it can be concluded that the submicron textures are effective for light trapping as well as for antireflection in thin c-Si solar cells if appropriate dimensions are chosen. Textures that are much smaller are not beneficial for light trapping; however, they can substantially reduce the surface reflectivity.

In general, RIE-textured surfaces are not perfect periodic structures and have some randomness. However, the results obtained in this study can be applied to the design of surface textures in c-Si solar cells with good optical properties, provided the solar cells possess dimensions such as a period equal to that of surface gratings.

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